EAST Search History

Ref #	Hits	Search Query	DBs	Default Operat or	Plural s	Time Stamp
L3	53	((dielectric insulat\$3) and (SiC \$iCOH (silicon near5 carbide)) and (oxide dioxide) and (trench via hole recess mesa groove) and (copper metal conduct\$3) and liner (polish\$3 CMP) and (etch\$3 pattern\$3) and (GCIB (gas near5 ion near5 beam)) and (protrud\$3 protrusion project\$3 (stick\$3 near2 out) and (wet near5 etch\$3))).clm.	US-PGPU B	OR	ON	2007/03/29 16:49